Investigation into Structure of Gallium-Selenide Nano Wires

Alison Hatt Prof. Marjorie Olmstead Prof. John Rehr University of Washington REU 2004

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Goals

- Primary goal: Determine the structure of gallium-selenide nano wires.
 - Use VASP software to compare energy of different possible structures.
- Short term goal: Calculate density of states for gallium-selenide.
 - Start with silicon, then arsenic terminated silicon.

Ga_xSe_y Observed Structures







- Two structures observed
 - Layered GaSe (left)
 - Defected zinc blende Ga₂Se₃
 (right)

🔘 Ga

🔘 Se

O Vacancy

$Ga_x Se_y$ on Silicon





← 350 nm → Layered GaSe showing cluster structure

← 400 nm →

 Ga_2Se_3 showing nano wire structure

(Images taken with scanning tunneling microscope)

Ga₂Se₃ nano wires



____ 100 **nm** ____



- Structure and growth mechanisms uncertain
- Electrical and optical properties untested
- Could have interesting device applications

Proposed Atomic Structure





- Wires run perpendicular to arsenic dimer rows
- Gallium atoms on top surface
- Two unit cell spacing

FEFF

Performs *ab initio* calculations of x-ray absorption and electronic structure

- Used to calculate local density of states (LDOS)
- Works with cluster in real-space
- Self-consistency loop method using atomic potentials



Density of States for Copper



Silicon 100



Cluster of eight unit cells of Si 100

- Created model using Cerius (molecule simulation software)
- A little bit of finagling to get it into a Feff input file

Silicon DOS

S-orbital DOS for Si atom in bulk of As terminated Si, computed with several cluster sizes Total electron count = 1.312



Silicon DOS: not yet reached convergence



Arsenic terminated Silicon



Cluster of eight unit cells of As:Si

- Model created using Cerius
- Arsenic atoms simply replacing silicon on 100 surface of diamond lattice

Arsenic terminated Silicon DOS

S-orbital DOS for As atom on As terminated Si, computed with several cluster sizes Total electron count = 1.553



Steps to take for LDOS calculations

- Drastically increase cluster size used in calculations
- Hydrogen terminate the bulk silicon
- Dimerize the arsenic (next slide)
- Add GaSe layer to model

Dimerize the Arsenic



QuickTime[™] and a TIFF (LZW) decompressor are needed to see this picture.

- Modify model to create dimer pairs between arsenic atoms.
- Re-run FEFF calculations to see if this alters the output significantly.

The next step: VASP



- Performs ab-initio quantum mechanical molecular dynamic
- Works in reciprocal space
- This tool should enable calculation and comparison of energy for possible structures of GaSe.

Conclusions and Future Steps

- FEFF is not well suited to DOS calculation for silicon
- VASP promises better success